

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Ando et al.  
Appl. No. : 10/572,709  
Filed : March 17, 2006  
For : POSITIVE RESIST  
COMPOSITION AND RESIST  
LAMINATE FOR OW-  
ACCELERATION ELECTRON  
BEAM AND METHOD OF  
PATTERN FORMATION  
Examiner : Schilling, R.  
Group Art Unit : 1795

CERTIFICATE OF EFS WEB  
TRANSMISSION

I hereby certify that this correspondence, and  
any other attachment noted on the automated  
Acknowledgement Receipt, is being transmitted  
from within the Pacific Time zone to the  
Commissioner for Patents via the EFS Web  
server on:

3/5/08  
(Date)

Neil S. Bartfeld, Ph.D., Reg. No. 39,901

**RESPONSE TO RESTRICTION REQUIREMENT****Mail Stop Amendment**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

In the Restriction/Election requirement mailed **February 19, 2008**, the Examiner restricted the pending claims into three patentably distinct inventions

- I. Claims 1-20, drawn to compositions, classified in class 430, subclass 270.1;
- II. Claims 21-39, drawn to image resist laminates, classified in class 430, subclass 14; and
- III. Claims 40-43, drawn to electron beam exposure, classified in class 430, subclass 296.

In response to the Restriction Requirement, Applicants hereby elect **Group I** (Claims 1-20), without traverse. Thus, claims 1-20 encompass the elected invention. Applicants reserve the right to pursue the remaining invention(s) in a divisional application(s).

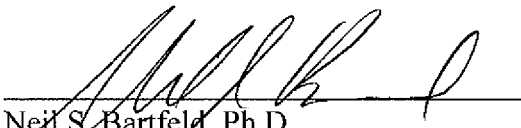
Appl. No. : 10/572,709  
Filed : March 17, 2006

No fees are believed to be due. However, please charge any additional fees, including any fees for additional extension of time, or credit overpayment to Deposit Account No. 11-1410.

Respectfully submitted,

KNOBBE, MARTENS, OLSON & BEAR, LLP

Dated: 3/5/08

By:   
Neil S. Bartfeld, Ph.D.  
Registration No. 39,901  
Agent of Record  
Customer No. 20,995  
(619) 235-8550

4971539  
030508